

# Supplementary Materials

Article

## Efficient Diode Performance with Improved Effective Carrier Lifetime and Absorption using Bismuth Nanoparticles Passivated Silicon Nanowires

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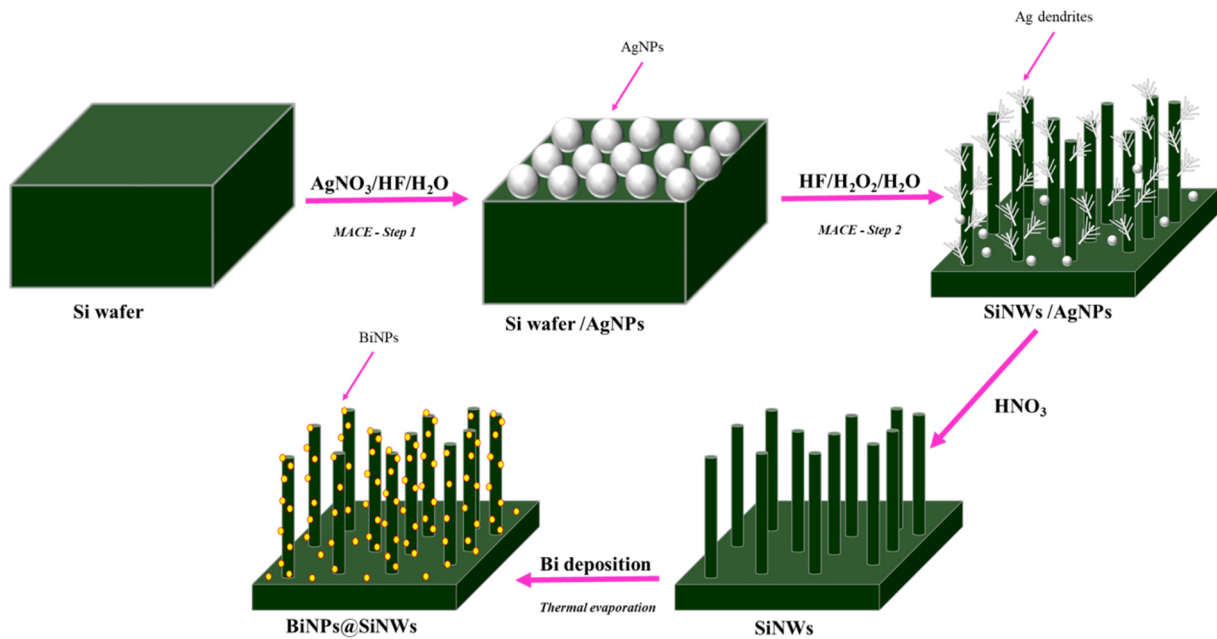
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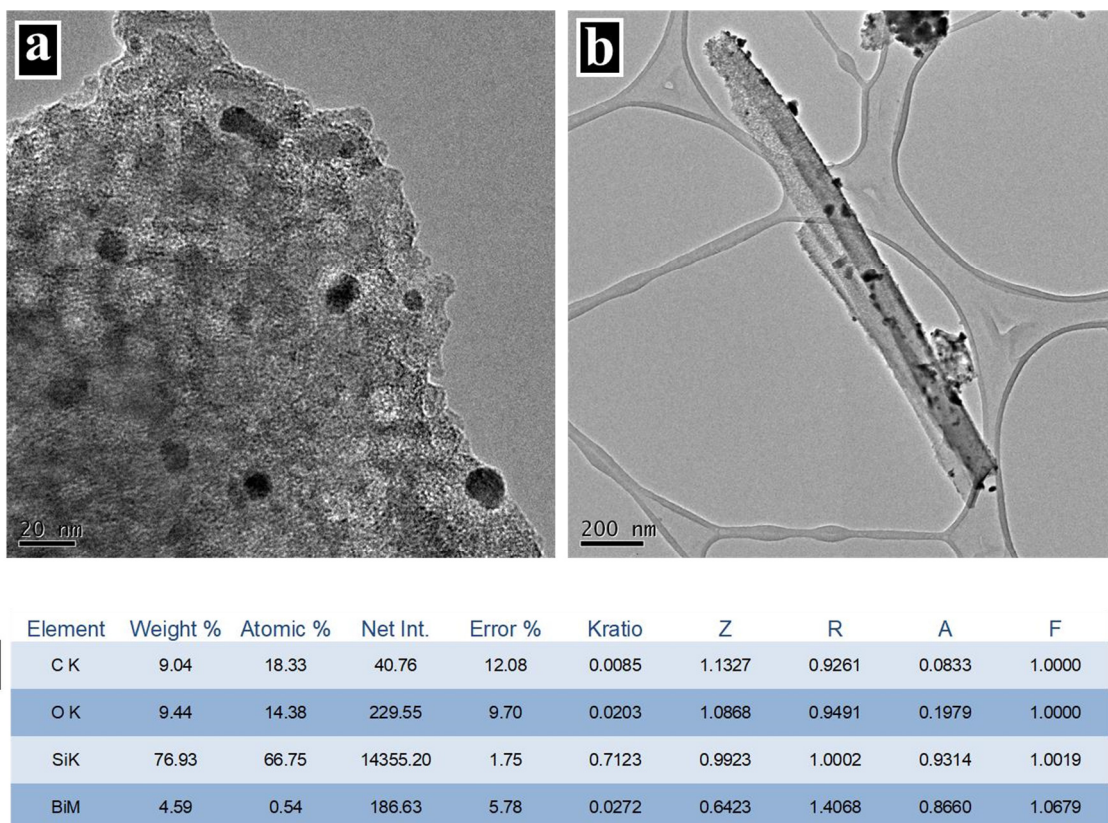
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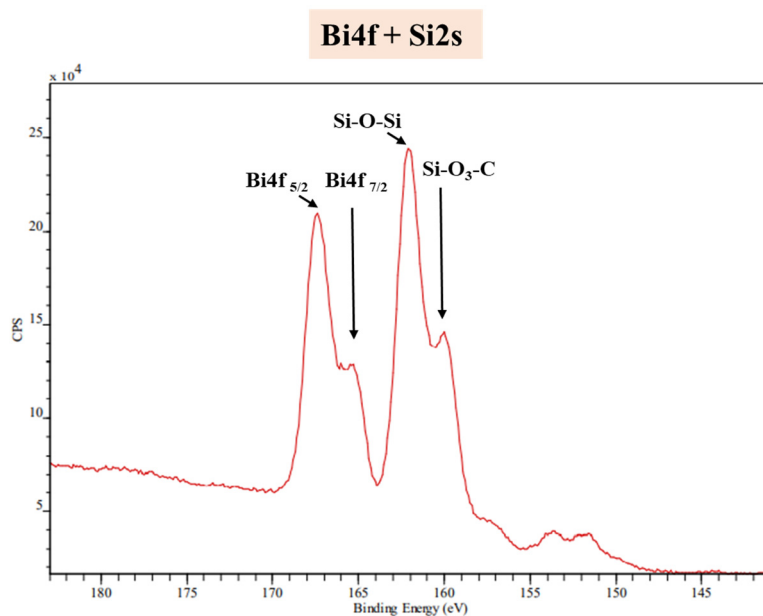
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**Figure S1.** Schematic illustration for the fabrication of BiNPs@SiNWs nanocomposite



**Figure S2. (a,b)** TEM images of Bi-rich SiNWs sample and **(c)** corresponding EDX table of the elemental concentration



**Figure S3. Deconvolution of Bi4f and Si2s XPS peaks**

**Table S1.** Comparison of Bi@SiNWs diode performance with other modified-SiNWs devices of various works

Devices	SiNWs formation technique	Material deposition technique	$\eta$ determination technique	$\eta$	references
Pt@SiNWs	MACE	Electroless deposition	conventional TE	9.61	[19]
Ag@SiNWs	MACE	Electroless deposition	conventional TE	7.78	[19]
Graphene@SiNWs	MACE	PECVD	conventional TE	3.92 ~ 5.52	[39]
Ag@SiNWs/polymer	MACE	Electroless deposition	conventional TE	2.16 ~ 2.41	[40]
Pt@SiNWs	MACE	Placing Pt Tip (monocontact)	conventional TE	3.7	[41]
Polymer@SiNWs	MACE	Spin coating	conventional TE	7.8	[42]
Bi@SiNWs	MACE	Thermal evaporation	conventional TE → Cheung's functions →	1.88 1.96	This work